	Appli ation No.	Applicant(s)	17
	10/707,261	HSU, PING	
Notice of Allowability	Examiner	Art Unit	
	Jennifer M. Kennedy	2812	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. X This communication is responsive to the amendment filed 11/23/2004.			
2. The allowed claim(s) is/are 1-7.			
3. The drawings filed on <u>02 December 2003</u> are accepted by	the Examiner.		
4.			
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/C Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ⊠ Interview Sumr Paper No./Mai 08), 7. ⊠ Examiner's Am	il Date <u>20050112</u> .	

Application/Control Number: 10/707,261

Art Unit: 2812

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Winston Hsu on January 11, 2005.

The application has been amended as follows:

Claims 8-10 have been cancelled.

The following is an examiner's statement of reasons for allowance: the prior art, either singly or in combination, fails to anticipate or render obvious, the method, including the limitations of removing said collar oxide layer that is not covered by said second polysilicon layer to expose said substrate at an upper portion of the said deep trench, and wherein a top surface of said second polysilicon layer and said exposed substrate define a second recess, filling said second recess with a spacer material layer, forming a photoresist layer on said spacer material layer, and said photoresist layer masking a portion of said spacer material layer, anisotropically etching said spacer material layer not covered by said photoresist layer, to form a single-sided spacer on the sidewall of said second recess, and performing a third polysilicon deposition and recess etching to embed a third polysilicon layer on said second polysilicon layer and said collar oxide layer, wherein dopants of said third polysilicon layer diffuse out to the surrounding substrate that is not masked by said single-sided spacer to form a non-

Application/Control Number: 10/707,261

Art Unit: 2812

annular buried strap out diffusion, in combination with the other limitations of independent claim 1.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jennifer M. Kennedy whose telephone number is (571) 272-1672. The examiner can normally be reached on Mon.-Fri. 8:30-5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Niebling can be reached on (571) 272-1679. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

ennifer M. Kennedy

Patent Examiner

Art Unit 2812